

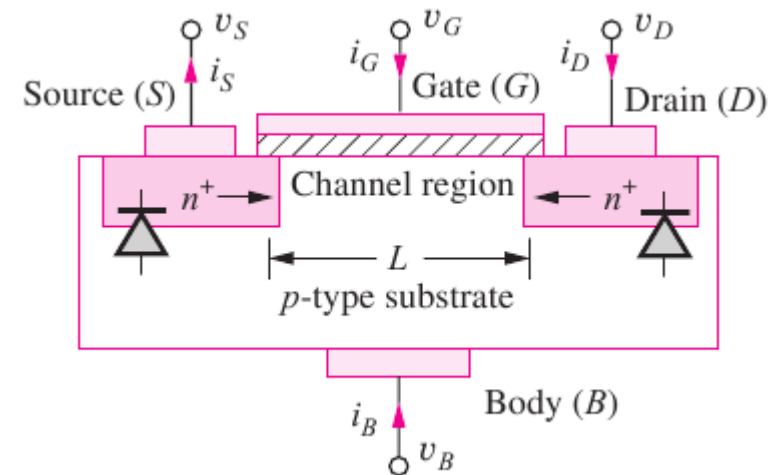
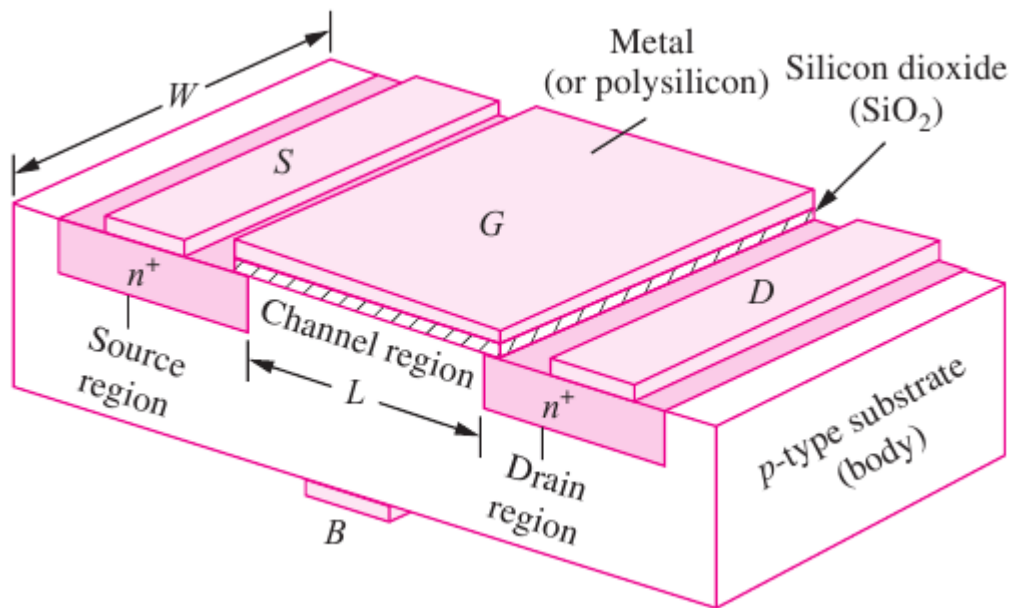
TE 046
DISPOSITIVOS ELETRÔNICOS

Oscar C. Gouveia Filho
Departamento de Engenharia Elétrica
UFPR

URL:
www.eletrica.ufpr.br/ogouveia/te046
E-mail: ogouveia@eletrica.ufpr.br

CAPÍTULO 6 - TRANSISTOR DE EFEITO DE CAMPO MOS

5.1 ESTRUTURA FÍSICA DO TRANSISTOR MOS

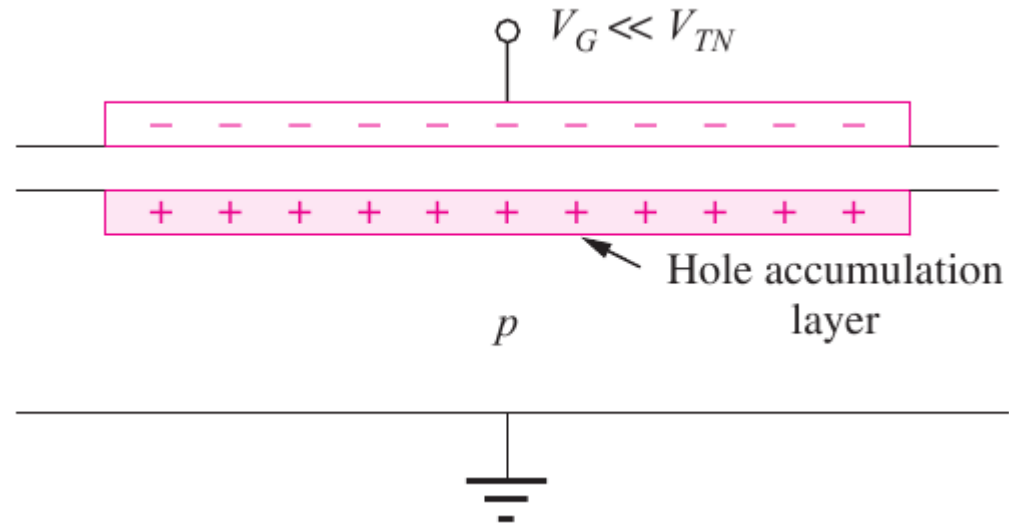


Desenho esquemático do MOSFET canal n

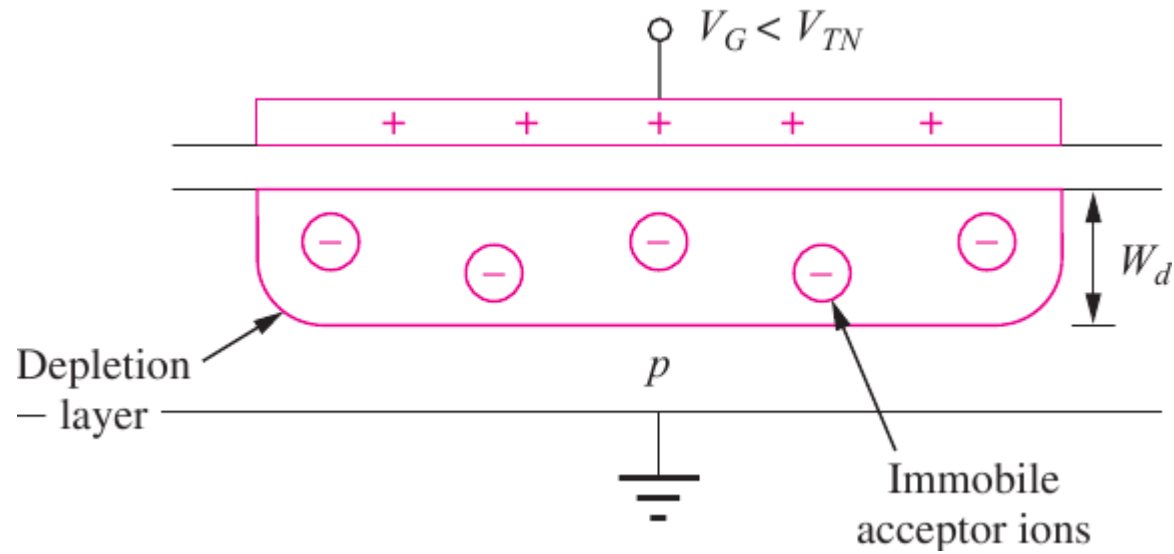
5.2 OPERAÇÃO DO TRANSISTOR MOS

5.2.1 O Capacitor MOS

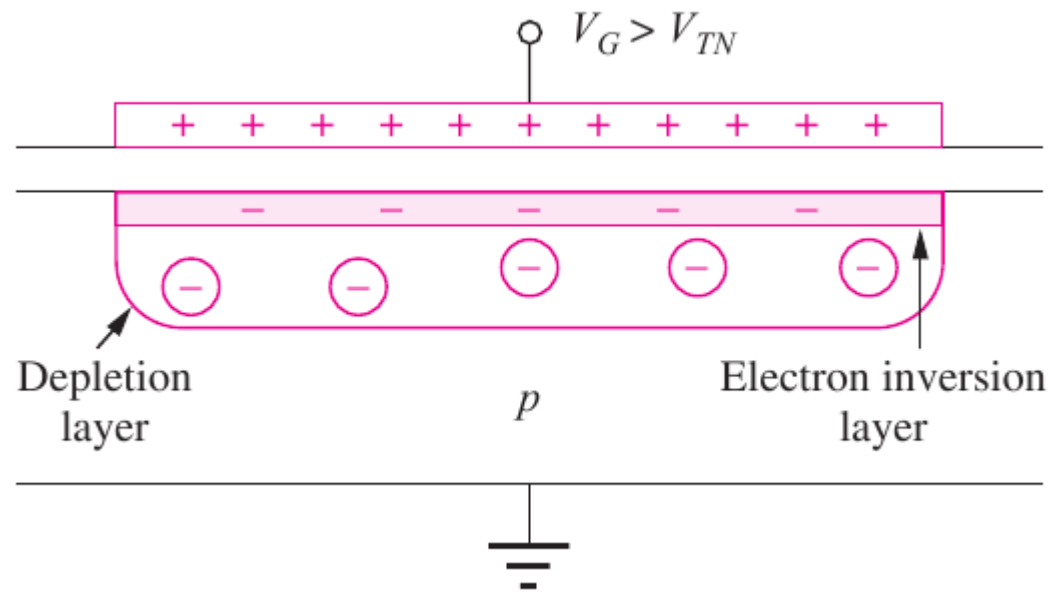
Acumulação



Depleção

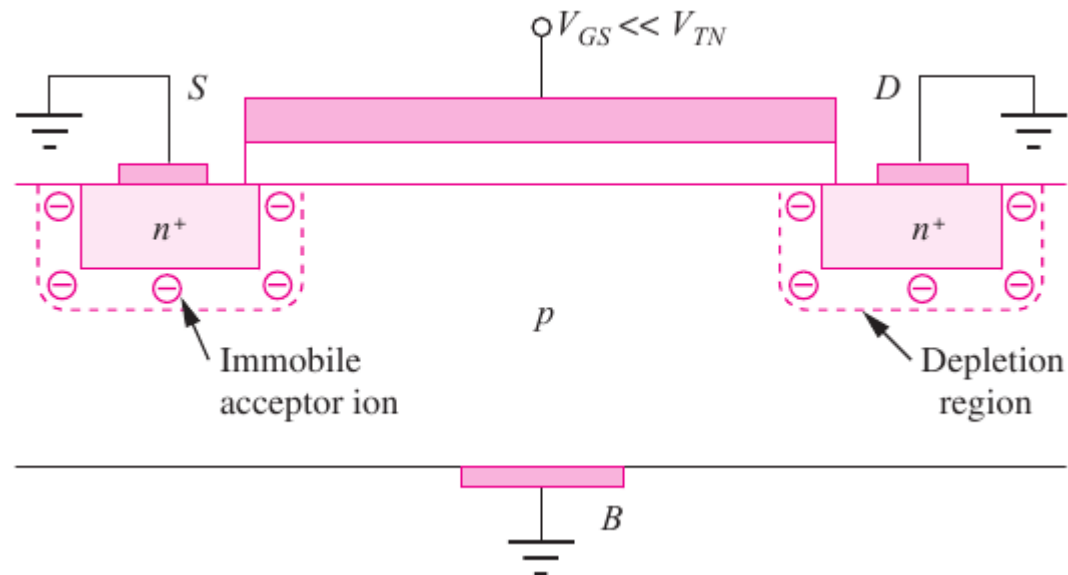


Inversão

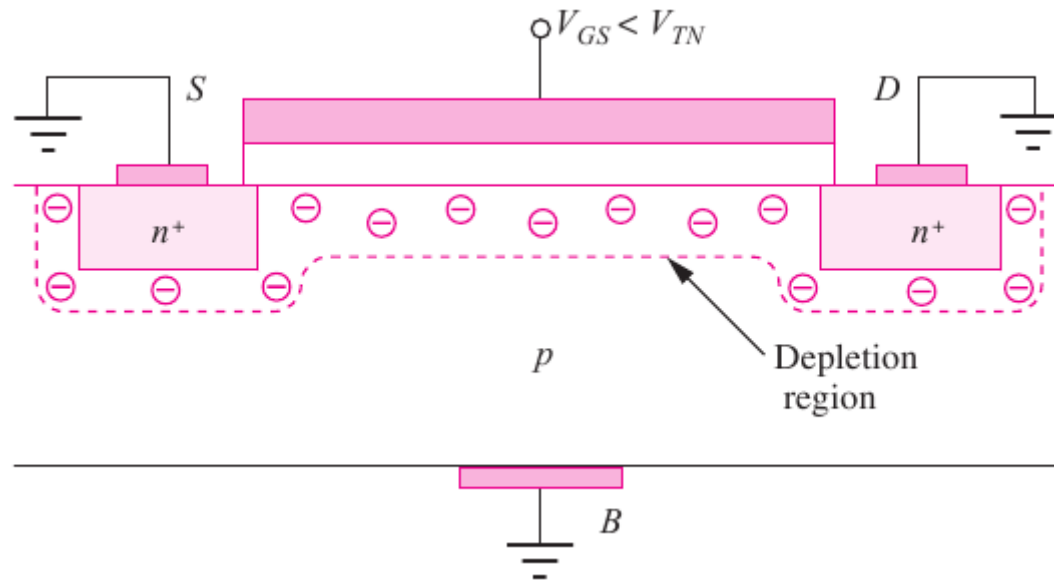


5.2.2 Análise Qualitativa do Transistor MOS

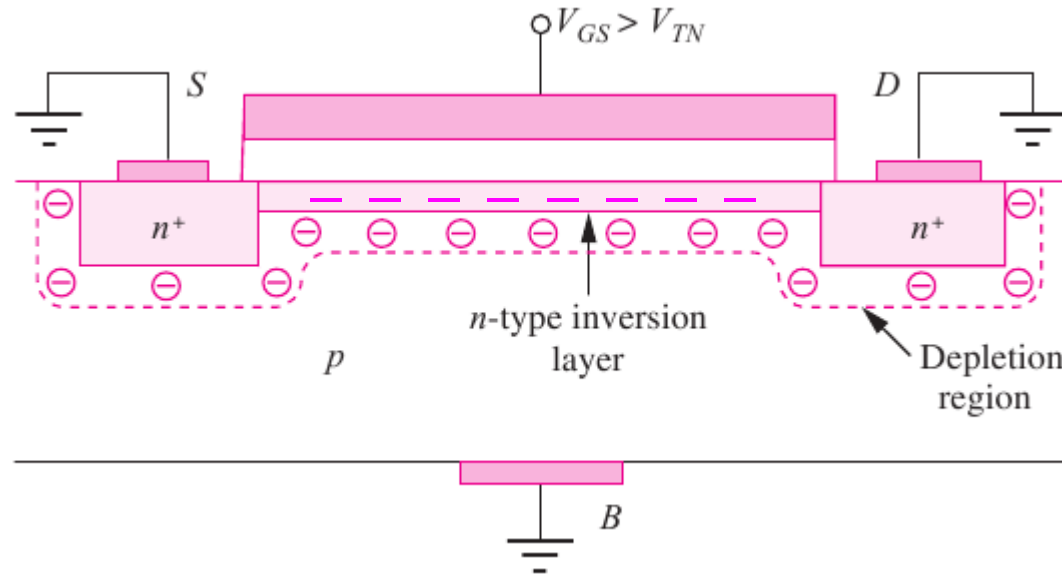
Acumulação



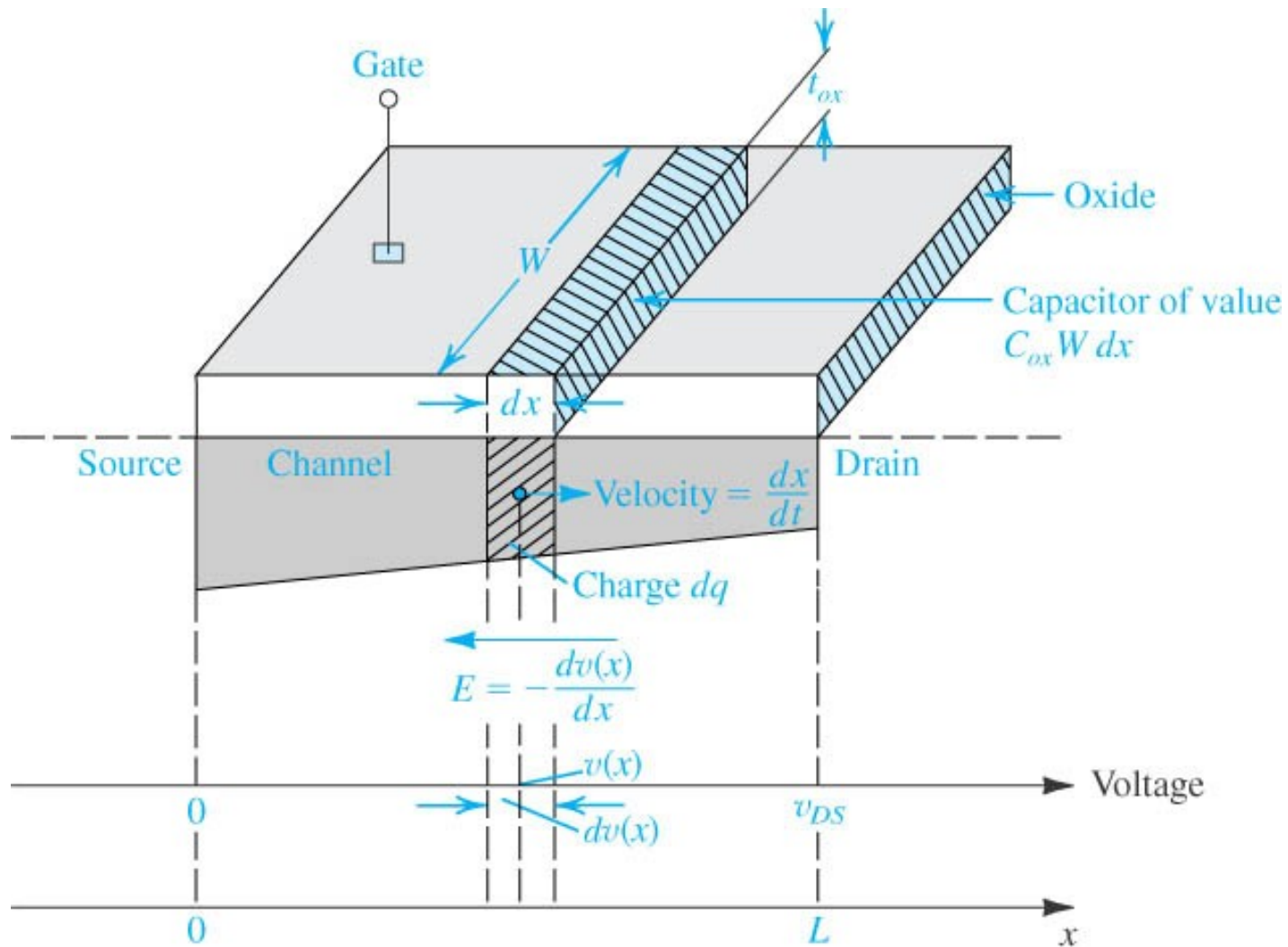
Depleção



Inversão



5.3 DETERMINAÇÃO DA CARACTERÍSTICA I-V DO MOSFET

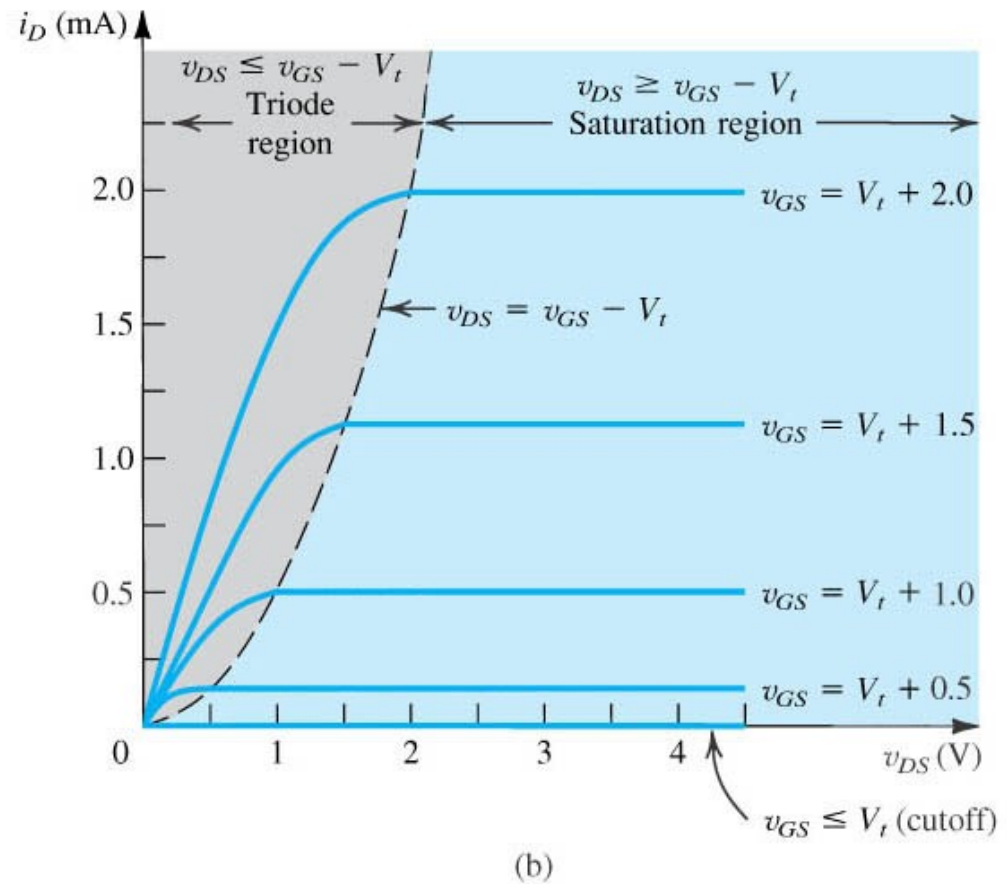
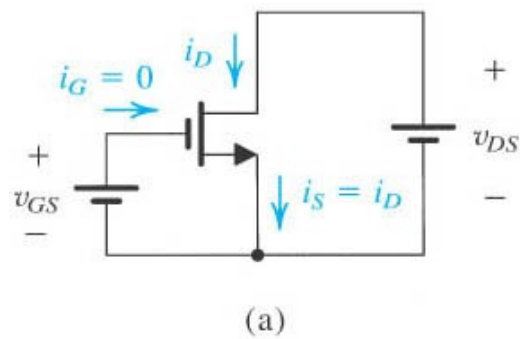


Exemplo: Considere um processo de fabricação MOS no qual $L_{min} = 0,18 \mu\text{m}$, $\mu_n = 440 \text{ cm}^2/\text{V}\cdot\text{s}$ e $V_T = 0,35 \text{ V}$.

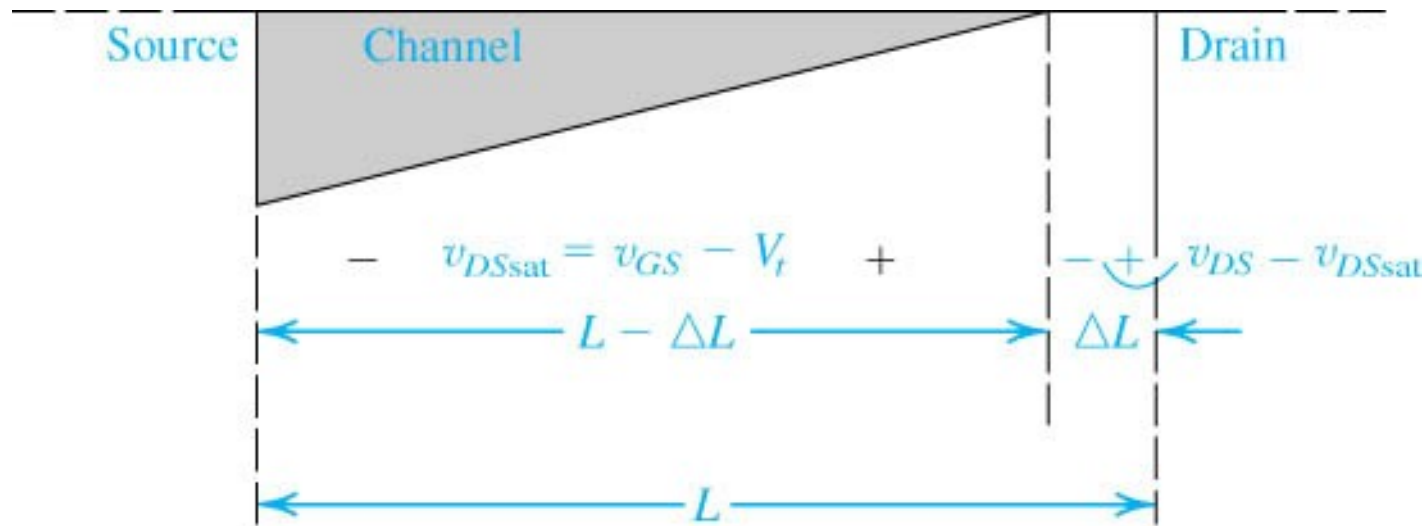
a) Para um MOSFET de $W/L = 2 \mu\text{m}/0,2 \mu\text{m}$ calcule V_{GS} e V_{DSmin} para operar o transistor na saturação com uma corrente de $25 \mu\text{A}$.

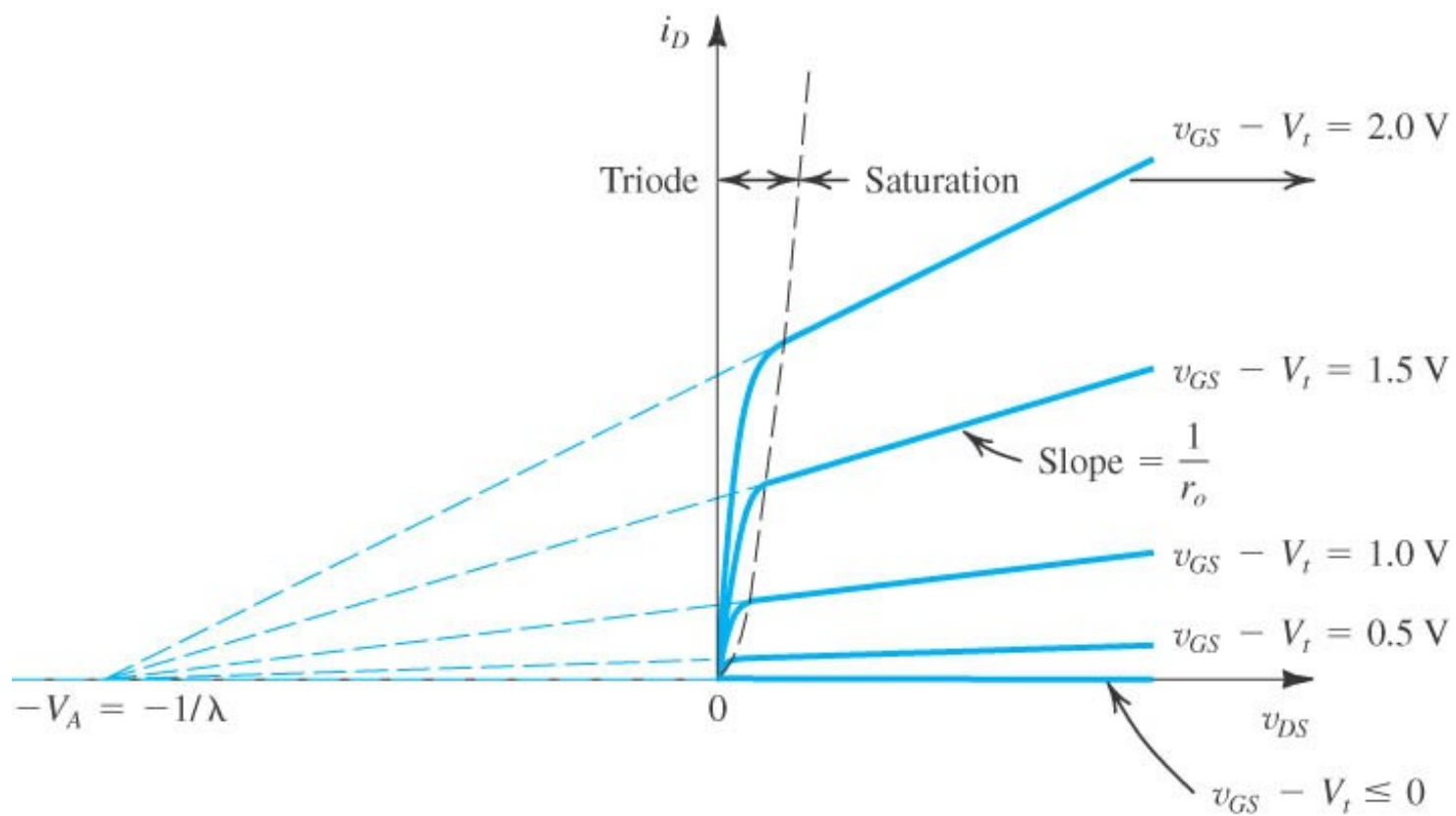
b) Para o dispositivo em a) ache o valor de V_{GS} necessário para operar o dispositivo como um resistor de 1000Ω , para V_{DS} muito pequeno.

5.3.1 Característica $I_D - V_{DS}$



5.3.2 Característica de saída na saturação (modulação do comprimento do canal)





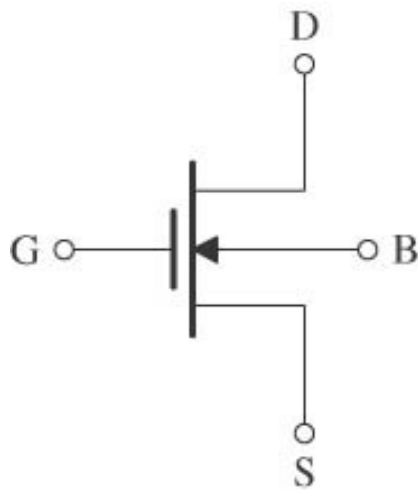
Resumo e Simbologia

Região triodo

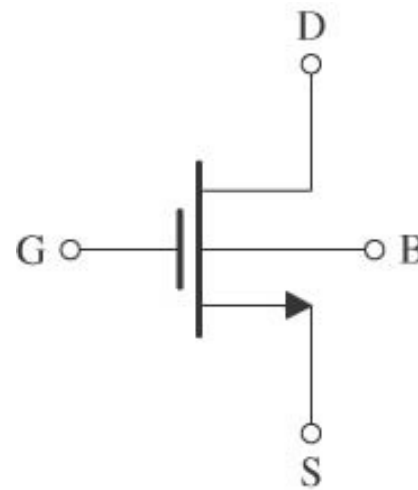
$$i_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} [(v_{GS} - V_{Tn}) v_{DS} - \frac{1}{2} v_{DS}^2]$$

Saturação

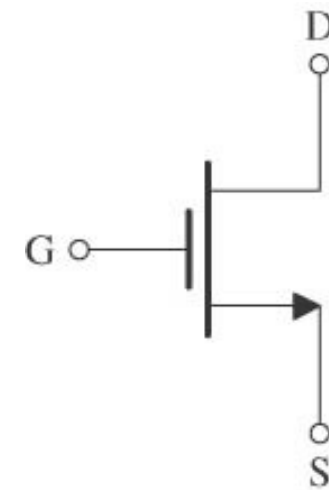
$$i_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (v_{GS} - V_{Tn})^2$$



(a)

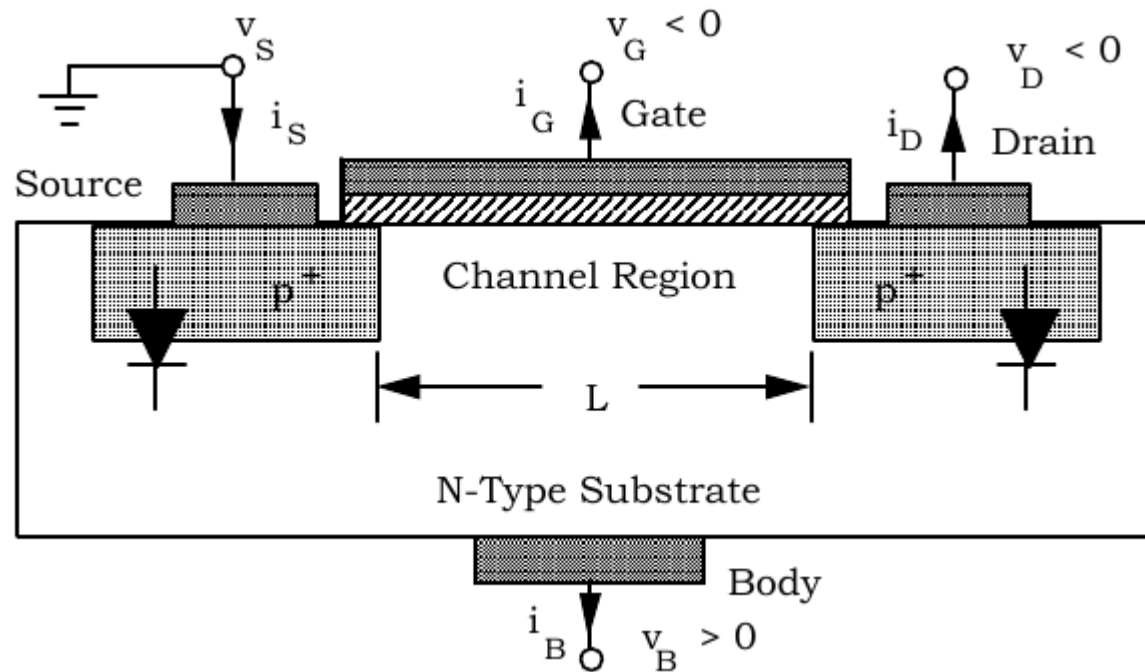


(b)

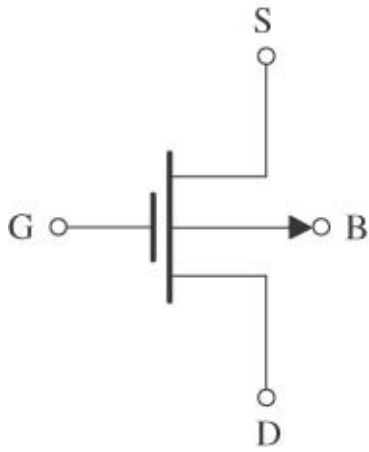


(c)

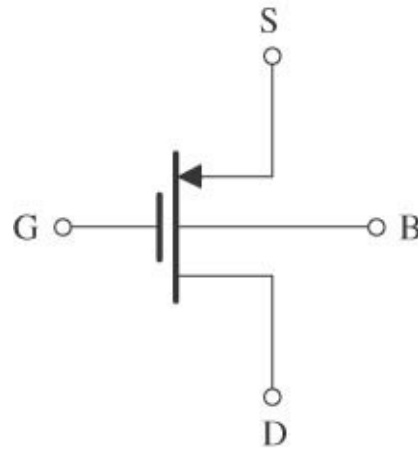
5.4 TRANSISTOR PMOS



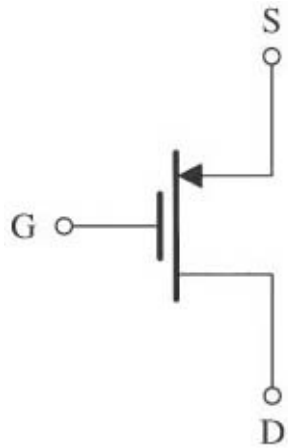
Resumo e Simbologia



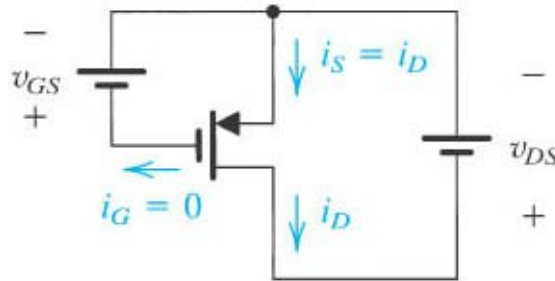
(a)



(b)



(c)



(d)

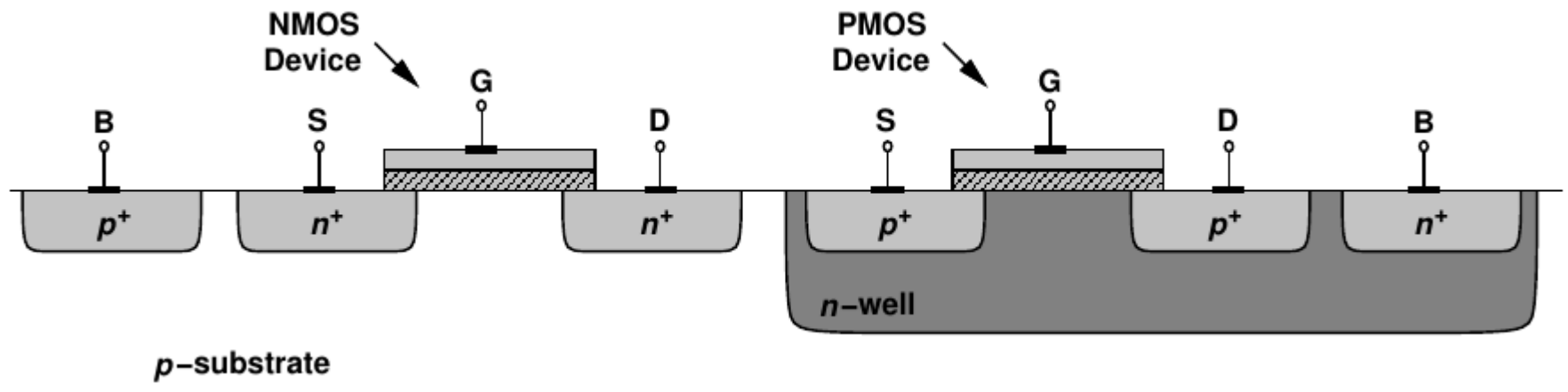
Região triodo

$$i_D = \frac{1}{2} \mu_p C_{ox} \frac{W}{L} [(v_{GS} - V_{Tp}) v_{DS} - \frac{1}{2} v_{DS}^2]$$

Saturação

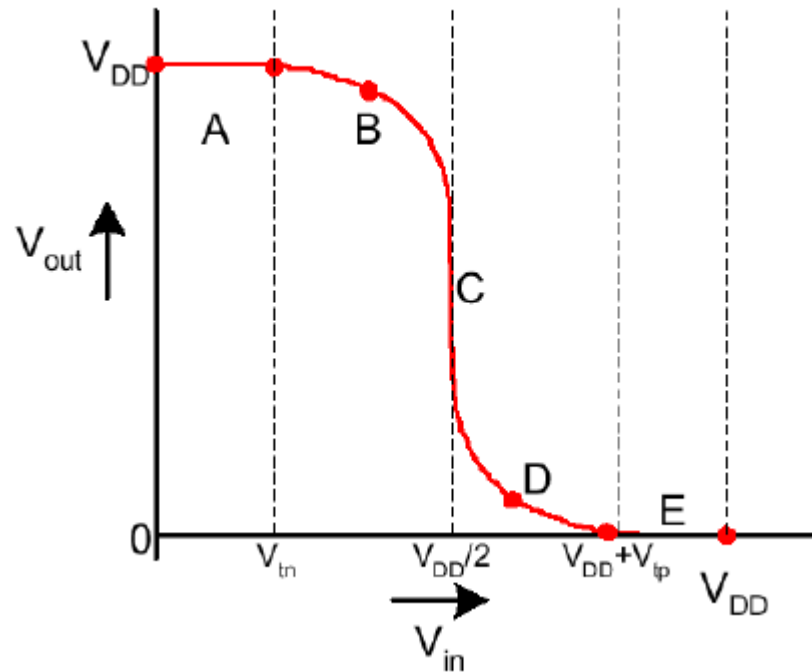
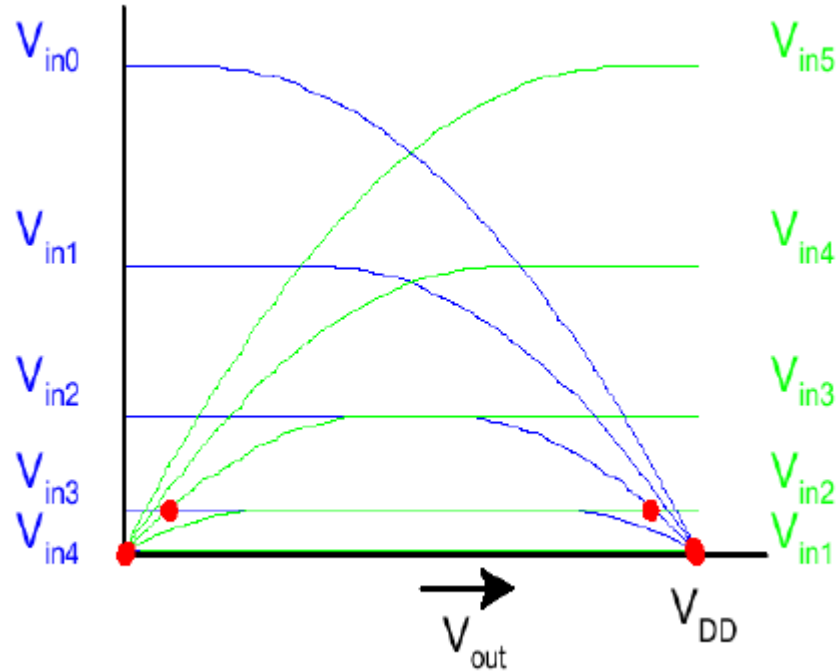
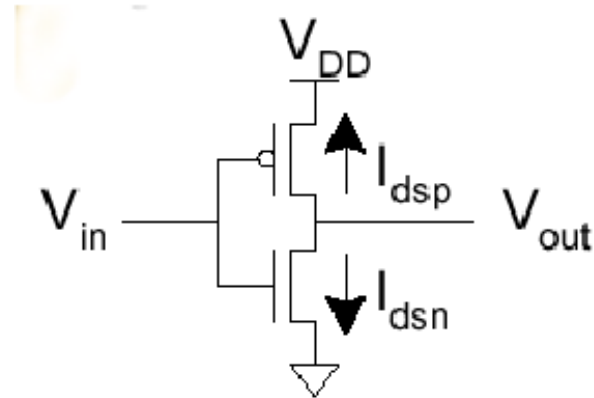
$$i_D = \frac{1}{2} \mu_p C_{ox} \frac{W}{L} (v_{GS} - V_{Tp})^2$$

5.5 TECNOLOGIA CMOS



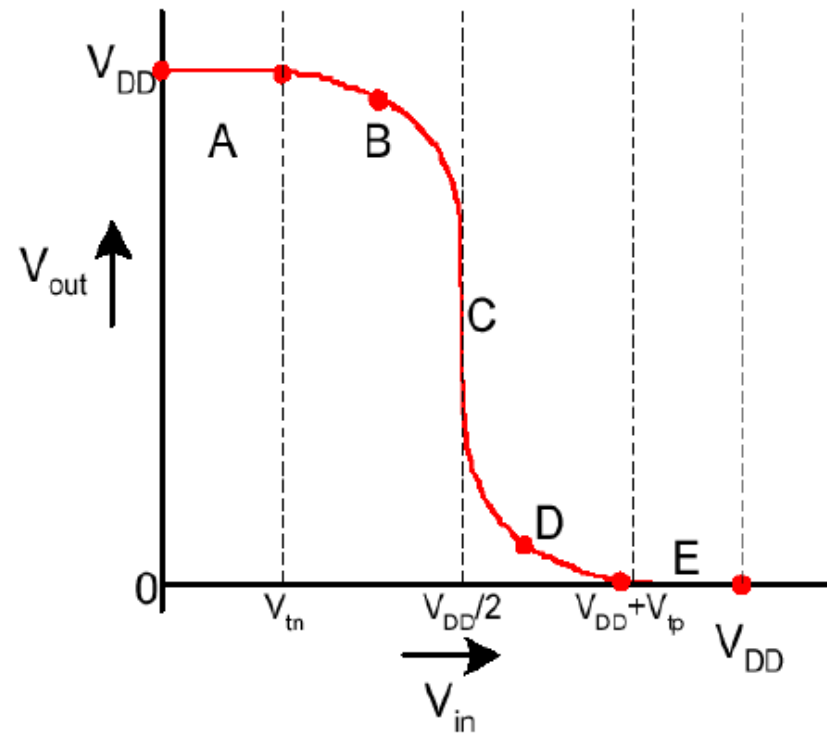
5.6 INVERSOR LÓGICO CMOS

CARACTERÍSTICA DE TRANSFERÊNCIA DC

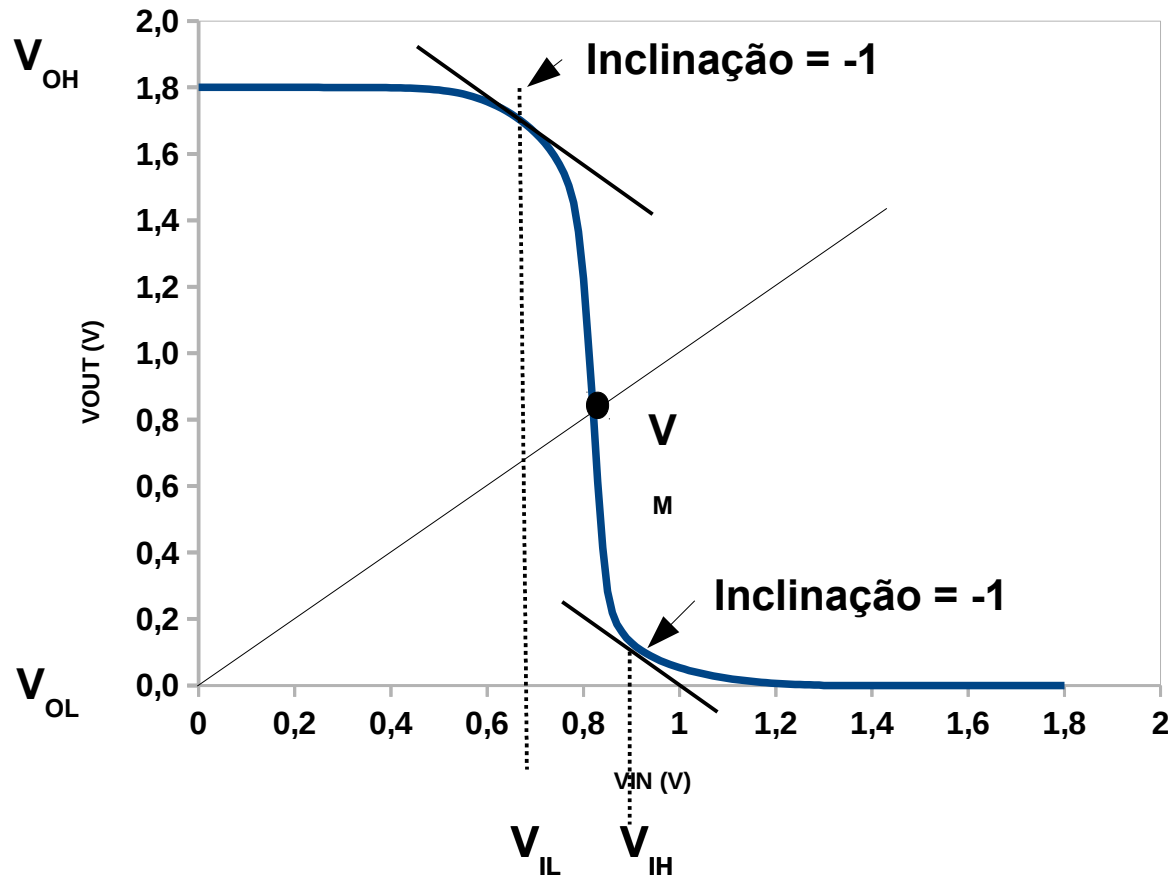


REGIÕES DE OPERAÇÃO

Region	nMOS	pMOS
A	Cutoff	Linear
B	Saturation	Linear
C	Saturation	Saturation
D	Linear	Saturation
E	Linear	Cutoff



NÍVEIS LÓGICOS



Determinação de V_M

Ambos transistores saturados

$$\frac{k_n}{2}(V_M - V_{tn})^2 = \frac{k_p}{2}(V_{DD} - V_M - |V_{tp}|)^2$$

$$V_M = \frac{r(V_{DD} - |V_{tp}|) + V_{tn}}{1 + r}$$

onde $r = \sqrt{\frac{k_p}{k_n}}$

$$k_{n(p)} = k'_{n(p)} \left(\frac{W}{L}\right)_{n(p)}$$

MARGENS DE RUÍDO

